What is claimed is:

1. An assembly for cathodic arc deposition of a material onto an article, the assembly comprising:

a chamber for receiving an article to be coated, the chamber being evacuated to a pressure below atmospheric pressure;

a rotatable target disposed within the chamber, the rotatable target having a surface from which a plasma material is ejected and a rotational axis;

an anode ring disposed in the chamber and positioned a first distance from the surface of the rotatable target, the anode ring having an opening extending through the anode ring, a central axis of the opening positioned parallel to the rotational axis of the rotatable target and offset a second distance from the rotational axis of the rotatable target; and

a spark device disposed in the chamber for generating an arc on the surface of the rotatable target,

wherein the assembly is configured to direct a stream of charged particles ejected from the surface of the rotatable target through the opening of the anode ring to the article to be coated.

2. The assembly according to claim 1, wherein the spark device has a distal end disposed between the opening of the anode ring and the surface of the rotatable target.

3. The assembly according to claim 1, further comprising:

a focus coil having a helical shape with an axis aligned with the central axis of the anode ring, the focus coil having a first end positioned at a third distance from the surface of the rotatable target;

a filter coil having a helical shape with an axis aligned with the central axis of the anode ring, the filter coil axially spaced from the first end of the focus coil; and

a limiter extending in a direction perpendicular to the central axis of the anode ring, the limiter positioned between the first end of the focus coil and the filter coil and having an opening that is axially aligned with the central axis of the anode ring.

4. The assembly according to claim 3, wherein the focus coil is disposed on an outer surface of the chamber.

5. The assembly according to claim 3, further comprising a filter duct attached to an open end of the chamber wherein the filter coil is disposed on an outer surface of the filter duct.

6. A method for coating an article using a cathodic arc deposition assembly, the cathodic arc deposition assembly comprising a target disposed within an evacuated chamber, the target having a surface from which a plasma material is ejected and a rotational axis, an anode ring disposed in the evacuated chamber and positioned a first distance from the surface of the target, the anode ring having an opening extending through the anode ring, a central axis of the opening positioned parallel to the rotational axis of the target and offset a second distance from the rotational axis of the target and a spark device disposed in the evacuated chamber for generating an arc on the surface of the target, the method comprising the steps of:

rotating the target about the rotational axis of the target; and

applying a voltage to the target and the anode to cause plasma to be ejected from the surface of the target and directed through the opening of the anode ring to the article.

7. The method according to claim 6, wherein the spark device has a distal end disposed between the opening of the anode ring and the surface of the rotatable target.

8. The method according to claim 6, wherein the voltage applied to the target and the anode is pulsed to generate a series of plasma pulses.

9. The method according to claim 6, the cathodic arc deposition assembly further comprises:

a focus coil having a helical shape with an axis aligned with the central axis of the anode ring, the focus coil having a first end positioned at a third distance from the surface of the target;

a filter coil having a helical shape with an axis aligned with the central axis of the anode ring, the filter coil axially spaced from the first end of the focus coil; and

a limiter extending in a direction perpendicular to the central axis of the anode ring, the limiter positioned between the first end of the focus coil and the filter coil and having an opening that is axially aligned with the central axis of the anode ring,

wherein prior to the step of applying a voltage, a step of:

applying a voltage to the filter coil to generate a uniform magnetic field for filtering the plasma ejected from the surface of the target.

10. The method according to claim 9, wherein the voltage applied to the target and the anode, the voltage applied to the filter coil and a voltage applied to the focus coil are pulsed to generate a series of plasma pulses.